## **Program LEELIS-III**

## 12th November 2018

9:35 - 9:40	Welcome Joost Frenken (ARCNL)
9:40 - 10:20 h	<b>Petra Swiderek</b> (Uni Bremen): Electron-induced Chemistry: Fundamentals and Applications in Nanofabrication
10:20 - 10:50 h	Coffee break (included in registration fee)
10:50-12:10 h	Armin Kleibert (PSI): X-ray photo-emission microscopy as a versatile tool for surface and interface investigations at the nanoscale Wolfgang Werner (TU Wien): Investigation of low energy electrons interacting with PMMA using one- and two-electron spectroscopies.
12:10 - 13:20 h	Lunch (included in registration fee)
13:20-15:20 h	Ivan Pollentier (Imec): Unraveling the chemical reactions of photoresists upon exposure with EUV  Greg Denbeaux (SUNY Polytechnic): Understanding secondary electrons interactions in chemically amplified EUV resists  Ivan Bespalov (ARCNL): Investigations of EUV resists with Low Energy Electrons Microscopy
15:20 - 17:30 h	Poster session
18:30 h	Dinner (included in registration fee)
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9:00 - 10:20 h	Ruben Maas (ASML): Accurate CD-SEM metrology for lithography Alex Vaglio Pret (KLA-Tencor): Modelling and simulation of electron scattering in organic and inorganic EUV lithography
10:20 - 10:40 h	Coffee break (included in registration fee)
10:40 – 11:40 h	Students talks x 3: Kerim Tugrul Arat, Yu Zhang & Carmen Popescu
11:40 - 12:20 h	<b>Petra Rudolf</b> (RUG): Electron-induced reactions for growth of novel materials
12:20 - 13:20 h	Lunch (included in registration fee) & posters
13:20 - 14:00	<b>Alex Guiliani</b> (SOLEIL): Electron impact activation of isolated ions in a linear ion trap
14:00 - 14:40h	<b>Ruud Tromp</b> (IBM): Low energy electron interactions with thin resist films - a new perspective
14:40 - 14:50 h	Poster Prize Award, close of meeting

15:00 - Option of a scenic boot-trip on the Amsterdam canals. (Not covered by registration fee, costs ~€20 p.p.)